

STABILIZED CYCLOSILOXANES FOR USE AS PRECURSORS FOR LOW-DIELECTRIC CONSTANT THIN FILMS

ABSTRACT

A siloxane dielectric precursor for use in a chemical vapor deposition (CVD) process, which has been dosed with a stabilizing agent(s) selected from free-radical inhibitors, end-capping agents and mixtures thereof. The stabilized siloxane dielectric precursor reduces the occurrence of premature deposition reactions occurring in the heated environment of the CVD delivery lines and process hardware.